

## IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Fuyuhiko INOUE, et al. : EXAMINER: STAFIRA, M. P.

SERIAL NO.: 10/080,537

RCE FILED: Herewith : GROUP ART UNIT: 2877

FOR: WAVEFRONT ABERRATION

MEASURING METHOD AND

UNIT, EXPOSURE APPARATUS, DEVICE MANUFACTURING METHOD, AND DEVICE

## **AMENDMENT**

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Notice of Allowance dated March 19, 2004, please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 31 of this paper.

Remarks/Arguments begin on page 41 of this paper.

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